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REMARKS

Claims 1-20 are pending in the application. New claims 15-20 are added with this paper.

The Office action restricts the invention to one of the following groups of claims:

I. Claims 1-13, drawn to a method; and

II. Claim 14, drawn to a device or apparatus.

In response, provisionally applicants elect to prosecute claims 1-13, with traverse, along with newly added method claims 15-20 drawn to the species of claims 1-13.

Applicants' traversal is based on MPEP 806.05(f), which reads as follows:

806.05(f) Process of Making and Product Made — Distinctness

A process of making and a product made by the process can be shown to be distinct inventions if either or both of the following can be shown: (A) that the process *as claimed* is not an obvious process of making the product and the process *as claimed* can be used to make other and different products; or (B) that the product *as claimed* can be made by another and materially different process.

Note the words "as claimed" (emphasis in the original). Claim 14 as claimed specifically recites an active matrix liquid crystal display device made according to

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claim 11. Thus the process of claim 11 is an obvious process of making the product of claim 14 as claimed because claim 14 specifically requires that it is the product of the method of claim 11, with only the additional structural features of an electrode structure spaced from the active plate, and liquid crystal disposed between the active plate and the further substrate. Similarly, the product of claim 14 as claimed can not be made by another and materially different process because claim 14 as claimed specifically recites that it must be made by the method of claim 11. Accordingly, withdrawal of the restriction requirement is respectfully requested.

Applicant(s) hereby conditionally cancel(s) the nonelected claim(s) 14 without prejudice or disclaimer of the subject matter thereof in the event the examiner maintains the restriction requirement. Applicant(s) reserve(s) the right to prosecute the subject matter of the canceled claim(s) in a divisional or other continuing application.

Remaining claim(s) are amended for non-statutory reasons, to place them in standard U.S. patent practice format.

Further examination of the application on its merits is respectfully requested. If any points remain in issue that may best be resolved through a personal or telephonic


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interview, the Examiner is respectfully requested to contact the undersigned at the telephone number listed below.

Respectfully submitted,


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VERSION WITH MARKINGS TO SHOW CHANGES MADE

In the claims:

1. (Amended) A method of improving electrical conductivity of lines ~~comprising of~~ transparent conducting material carried on a substrate, ~~comprising the step of:~~
forming the lines of transparent conducting material on the substrate ~~and;~~
providing on the upper surface of each of the lines a covering layer extending from an end part of the line and partially covering the upper surface of the line, ~~and the step of~~
subjecting the lines to a metal electroplating process in which a plating potential is applied to each line at the end part whereby a metal layer is plated on the exposed surface area of the line, the covering layer serving to shield the underlying surface of the line during the plating.

2. (Amended) ~~A method according to Claim~~ The method of claim 1, wherein the covering layer is shaped such that the exposed surface of the line increases progressively away from the end part.

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3. (Amended) ~~A method according to Claim~~ The method of claim 2, wherein the covering layer tapers in width away from the end part.

4. (Amended) ~~A method according to Claim~~ The method of claim 2, wherein the covering layer is stepped in width along the line.

5. (Twice Amended) ~~A method according to~~ The method of claim 1, wherein the covering layer extends from both ends of the line in similar manner and the plating potential is applied at both ends of the line during the plating process.

6. (Twice Amended) ~~A method according to~~ The method of claim 1, wherein the covering layer comprises photoresist.

7. (Twice Amended) ~~A method according to~~ The method of claim 1, wherein the step of forming the lines comprises:
depositing a layer of transparent conducting material
(53) over the substrate (46),

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depositing a photoresist layer ~~(54)~~ over the layer of transparent conducting material and patterning the photoresist into a configuration corresponding to the desired lines, and patterning the transparent conducting layer using the photoresist to leave the lines of transparent conducting material.

8. (Amended) ~~A method according to Claim~~ The method of claim 7, wherein the photoresist layer is patterned into portions corresponding to the desired lines with each portion including a selected region having a first thickness and conforming with the form of the required covering layer with the remainder of the portion being of reduced thickness, and after patterning the transparent conducting layer the photoresist is partially etched to remove the areas of reduced thickness while leaving photoresist at the selected region which photoresist constitutes the covering layer.

9. (Twice Amended) ~~A method according to~~ The method of claim 7, and for use in the manufacture of a pixellated device comprising pixel electrodes ~~(38)~~ of transparent conducting material carried together with the conductive lines on the substrate ~~(46)~~, wherein the photoresist layer ~~(54)~~ is

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patterned into a configuration corresponding also to the desired pixel electrodes, and wherein the transparent conducting layer—(53)—is patterned using the photoresist to leave pixel electrode regions—(57).

10. (Amended) ~~A method according to Claim~~ The method of claim 9, wherein photoresist is left over the pixel electrode regions during the electroplating process.

12. (Amended) ~~A method according to Claim~~ The method of claim 11, wherein the photoresist layer is patterned into areas of different thicknesses at the conductor lines and wherein the step of defining the photoresist comprises partially etching the photoresist to remove the thinner areas.

13. (Twice Amended) ~~A method according to~~ The method of claim 11, wherein the photoresist is defined to leave on each line a similar photoresist region extending from the other end part and wherein the plating potential is applied also at that other end part.

14. (Twice Amended) An active matrix liquid crystal display device comprising an active plate—(82) made according

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to claim 11, a further substrate ~~(83)~~ carrying an electrode structure spaced from the active plate, and liquid crystal ~~(81)~~ disposed between the active plate and the further substrate.

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